AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions and listings of claims in the application:

1.   (Currently Amended)   A method of producing a semiconductor device upon receiving an order for the semiconductor device by transferring information between a person who wishes to receive an order and a person who wishes to place an order through a network, the method comprising:

causing the person who [[wises]] wishes to place an order to input specifications of the semiconductor device by request of the person who wishes to [[place]] receive an order;

generating a plurality of circuit patterns in consideration of conditions for transferring a pattern by charged-particle beam exposure of a character projection method based on the specifications of the semiconductor device, based on the specifications of the semiconductor device, the circuit patterns including a circuit pattern generated by using a stored character projection (CP) aperture for charged-particle beam exposure and a circuit pattern generated by using the stored CP aperture and a CP aperture to be newly produced, and obtaining at least two a plurality of design parameters for each of the circuit patterns, and calculating a cost and a delivery time period for each of the circuit patterns, the cost including a cost for producing the CP aperture to be newly prepared; and

presenting said at least two plurality of design parameters and the cost and the delivery time period for each of the circuit patterns to the person who wishes to place an

order for each of the circuit patterns and causing the person who wishes to place an

order to select a circuit pattern satisfying a desired condition.

2-3.   (Cancelled)

4.   (Original)   The method according to claim 1, further comprising:

requesting a device maker to generate the selected circuit pattern through the network

after the circuit pattern is ordered by the person who wishes to place an order.

5.   (Currently Amended)   The method according to claim 1, further

comprising: requesting a CP aperture maker to produce a the CP aperture ~~necessary~~

~~for generating the selected circuit pattern~~ to be newly produced through the network

after the circuit pattern is ordered by the person who wishes to place an order.

6.   (Currently Amended)   A method of producing a semiconductor device

upon receiving an order for the semiconductor device based on information transferred

between a person who wishes to receive an order and a person who wishes to place an

order through a network, the method comprising:

causing the person who [[wises]] wishes to place an order to input specifications

of the semiconductor device by request of the person who wishes to [[place]] receive an

order;

transmitting the specifications of the semiconductor device to a server, and

causing the server to generate a plurality of circuit patterns ~~in consideration of~~

~~conditions for transferring a pattern by charged-particle beam exposure of a character projection method based on the specifications of the semiconductor device~~ based on the specifications of the semiconductor device, the circuit patterns including a circuit pattern generated by using a stored CP aperture for charged-particle beam exposure and a circuit pattern generated by using the stored CP aperture and a CP aperture to be newly produced, and to obtain ~~at least two~~ a plurality of design parameters for each of the circuit patterns;

receiving said ~~at least two~~ plurality of design parameters from the server; and

presenting said ~~at least two~~ plurality of design parameters to the person who wishes to place an order for each of the circuit patterns and causing the person who wishes to place an order to select a circuit pattern satisfying a desired condition.

7-9.   (Cancelled)

10.   (Currently Amended)   A program product for causing a computer system to produce [[the]]a semiconductor device upon receiving an order for the semiconductor device by transferring information between a person who wishes to receive an order and a person who wishes to place an order through a network, the program product comprising:

a recording medium; and

first, second, and third instruction means which [[is]]are operated by the computer system and [[is]]are recorded on the recording medium, wherein

the first instruction means provides the computer system with an instruction to

cause the person who wishes to place an order to input specifications of the

semiconductor device by request of the person who wishes to [[place]] receive an order;

the second instruction means ~~generate~~ generates a plurality of circuit patterns ~~in~~

~~consideration of conditions for transferring a pattern by charged-particle beam exposure~~

~~of a character projection method based on the specifications of the semiconductor~~

~~device~~ based on the specifications of the semiconductor device, the circuit patterns

including a circuit pattern generated by using a stored CP aperture for charged-particle

beam exposure and a circuit pattern generated by using the stored CP aperture and a

CP aperture to be newly produced, and obtains ~~at least two~~ a plurality of design

parameters for each of the circuit patterns; and

the third instruction means presents said ~~at least two~~ plurality of design

parameters to the person who wishes to place an order for each of the circuit patterns

and causes the person who wishes to place an order to select a circuit pattern satisfying

a desired condition.

11.   (Currently Amended)   A data signal which is embodied by a carrier,

for allowing a semiconductor device to be produced upon receiving an order for the

semiconductor device based on information transferred between a person who wishes

to receive an order and a person who wishes to place an order through a network, the

data signal comprising:

a first program code portion which is configured to cause the person who wishes to place an order to input specifications of the semiconductor device by request of the person who wishes to receive an order;

a second program code portion which is configured to generate a plurality of circuit patterns ~~in consideration of conditions for transferring a pattern by charged-particle beam exposure of a character projection method based on the specifications of the semiconductor device~~ based on the specifications of the semiconductor device, the circuit patterns including a circuit pattern generated by using a stored CP aperture for charged-particle beam exposure and a circuit pattern generated by using the stored CP aperture and a CP aperture to be newly produced, and obtain ~~at least two~~ a plurality of design parameters for each of the circuit patterns; and

a third program code portion which is configured to present said ~~at least two~~ plurality of design parameters to the person who wishes to place an order for each of the circuit patterns and cause the person who wishes to place an order to select a circuit pattern satisfying a desired condition.